

AMENDMENTS TO THE SPECIFICATION:

Please amend the paragraph beginning at page 4, line 12 as set forth below:

According to the present invention, the reference point of the substrate is positioned against the transfer arm and the location ~~relationship of the~~ of each wave guide of each plasma unit in relation to the transfer direction of the transfer arm is the same for each plasma processing apparatus, so that the location ~~relationship~~ of the wave guide relative to the reference point of the substrate is the same between the plasma processing units. Therefore, even if the electric field intensity distribution of high frequency waves introduced from the wave guide is deviated and the plasma concentration on the basis of it is not uniform, there is no difference in the effect of the deviation of the electric field intensity distribution for the substrate between the plasma processing units. Therefore, analysis of the processing condition and improvement of the apparatus can be easily carried out.

Please amend the paragraph beginning on page 7, line 10 as set forth below:

A characteristic of this embodiment is that in both the plasma processing units 3A and 3B, the wave guide 5 has the same structure, that is, the volume and length of the wave guide 5 are the same and the location ~~relationship~~ of the wave guide 5 relative to the wafer W mounted on the mounting stage 4 in a predetermined direction is the same. Namely, the volume and height of the cylindrical wave guide 52 and the conical wave guide 53 are the same in either of the plasma processing units 3A and 3B and the structure and shape of the rectangular wave guide 51 are also the same. Furthermore, as shown in Fig. 4, as viewed in the plane shape (viewed from the top), the location ~~relationship~~ of the rectangular wave guide 51 relative to the axial lines M1 and M2 connecting the center 4a of the mounting stage 4 and the center 22a of the width of the transfer port 22 is the same. In the plasma processing apparatus shown as a conventional example, the rectangular wave guides of both the plasma processing units are arranged symmetrically right and left and the embodiment of the present invention is different in this respect.

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